

Please substitute the following amended claims for corresponding claims previously presented. A copy of the amended claims showing current revisions is attached.

8. A method of fabricating a porous filter element according to claim 1, wherein the step of treating the exposed photosensitive material to selectively remove regions thereof comprises removing regions having an exposure below a predetermined level.

$$A^2$$

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11. A method of fabricating a porous filter element according to claim 1, wherein the pattern varies through the depth of the material to vary the cross-section of said regions through the depth of the material.

12. A method of fabricating a porous filter element according to claim 10, wherein the pattern repeats across the material perpendicular to the depth direction to create in the material a regular array of identical regions which extend through the depth of the material.

A¹
13. A method of fabricating a porous filter element according to claim 1, wherein the material is a mixture of an epoxy resin and a photoacid generator.

14. A method of fabricating a porous filter element according to claim 1, wherein the material to be exposed is in the form of a thin film.

15. A method of fabricating a porous filter element according to claim 1 wherein the photosensitive material comprises a plurality of regions of different composition such that the different regions react differently to exposure followed by treatment.

17. A method of fabricating a porous filter element according to claim 1,

A² comprising the further step of using said treated material as a lost mould to form a porous filter element.

20. A method according to claim 1 wherein the exposure time and/or

intensity of the e.m. radiation is set selectively in accordance with the desired size of the

A³ regions.

21. A porous filter element made by the method of claim 1.